Soft X-Ray Emission and Absorption Spectra in the Si L Region of Polysilanes

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Substituted polysilanes, (SiRR')n, have attracted significant attention because of their unique electronic properties. Their characteristic electronic nature arises from band edge structures which are composed of valence and conduction bands from σ and σ^* bands, respectively, which differ from the electronic structure of polyacetylene. To further understand their electronic properties, we have measured the Si L x-ray emission spectra of a number of polysilanes with alkyl and phenyl substituents. In addition, their x-ray absorption spectra have also been measured to obtain information regarding unoccupied electronic orbitals.

Chemically synthesized polysilanes, $(SiR_2)n$, where R indicates substitution with a methyl (Me; CH₃), ethyl (Et; C₂H₅), propyl (Pr; n-C₃H₇), butyl (Bu; n-C₄H₉), pentyl (Pe; n-C₅H₁₁) or phenyl (Ph; C₆H₅) group, were used for spectroscopic measurements. Soft x-ray emission spectra in the Si L region were measured using a grating x-ray spectrometer installed in the undulator beamline, BL-8.0.1. The photon energy of the monochromatized incident beam was tuned to about 130 eV to effectively excite Si2p-electrons while preventing multiple ionizations. Total-electron-yield (TEY) x-ray absorption spectra were obtained by monitoring sample photocurrent in BL-6.3.2. Measured x-ray emission and absorption spectra were analyzed using discrete variational (DV)-X α molecular orbital calculations.

Figure 1 shows soft x-ray emission and absorption spectra in the Si L region of both the polysilanes and the reference compounds, Si and SiO₂. In the emission spectra, polysilane spectral features exhibited similar structures; a main peak near 90 eV, and high-energy and lowenergy shoulders clearly differ from those of the Si and SiO₂ references. In absorption spectra, alkyl-substituted polysilanes exhibit a threshold energy of 101 eV, while the Ph-substituted polysilane exhibits a slightly lower threshold energy. In the fine-structure at the thresholds of polysilanes, a pre-edge peak is observed near 101 eV and an intense peak is seen at 102 eV for the Ph-substituted polysilane. No such pre-edge or intense peaks, however, are observed in the spectra of alkyl-substituted samples. From spectral analysis using DV-Xα molecular orbital calculations Si L x-ray emission spectra, which include a main peak with high- and low-energy shoulders, are explained by the summed DOS spectra of occupied Si3s and Si3d orbitals hybridized with Si3p, C2s and C2p orbitals. X-ray absorption spectra are also qualitatively explained by the summed DOS spectra of unoccupied Si3s and Si3d orbitals. In both x-ray emission and absorption spectra, little difference is observed among alkyl-substituted polysilanes. It is therefore confirmed that the length of alkyl substituents has little effect on the electronic structure of the Si backbone. X-ray spectral features of the Ph-substituted polysilane, however, slightly differ from alkyl-substituted features. This is explained by the difference in hybridization of Si and C orbitals between sp²-C atoms in phenyl substituents and sp³-C atoms in alkyl ones.

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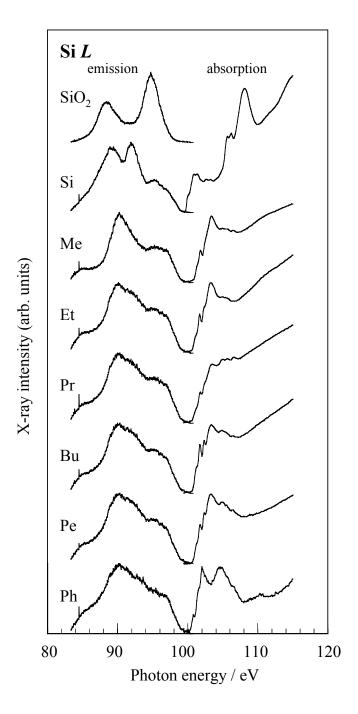


Figure 1 Soft x-ray emission and TEY x-ray absorption spectra in the Si L region of the polysilanes, (SiR₂)n, and Si and SiO₂ reference compounds. Substituents in the polysilanes, R, are denoted by Me (CH₃), Et (C₂H₅), Pr (n-C₃H₇), Bu (n-C₄H₉), Pe (n-C₅H₁₁), and Ph (C₆H₅).